

Low-Cost Direct Bonded Aluminum (DBA) Substrates

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Project ID #:
PM036

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Overview

Timeline

- **Project start: October 2010**
(actual funding starts: Jan 2011)
- **Project end: September 2013**
- **Percent complete: 75%**

Budget

- **Total project funding**
 - DOE 100%
- **FY11: \$200k**
- **FY12: \$200k**
- **FY13: \$130k (\$80k allocated to-date)**

Barriers*

- **High cost per kW**
- **Low energy per kg**
- **Low energy density**
- **Insufficient performance and lifetime**

Targets

- **DOE VTP* 2020 target: \$3.3/kW**
- **DOE VTP* 2020 target: 14.1 kW/kg**
- **DOE VTP* 2020 target: 13.4 kW/l**
- **15 year life**

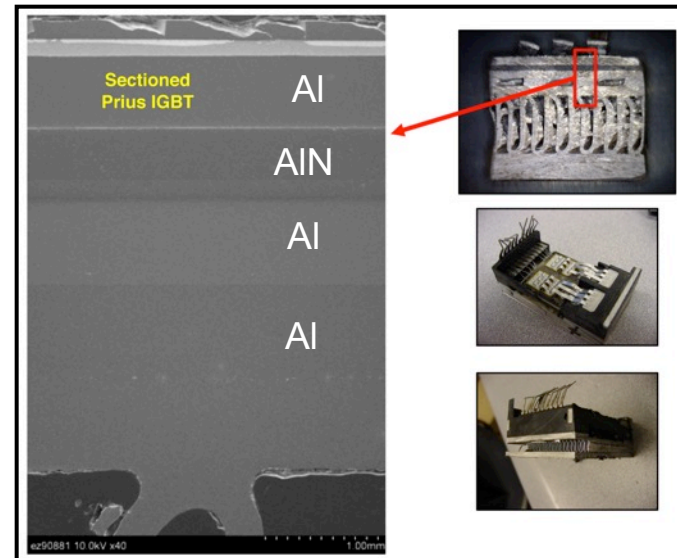
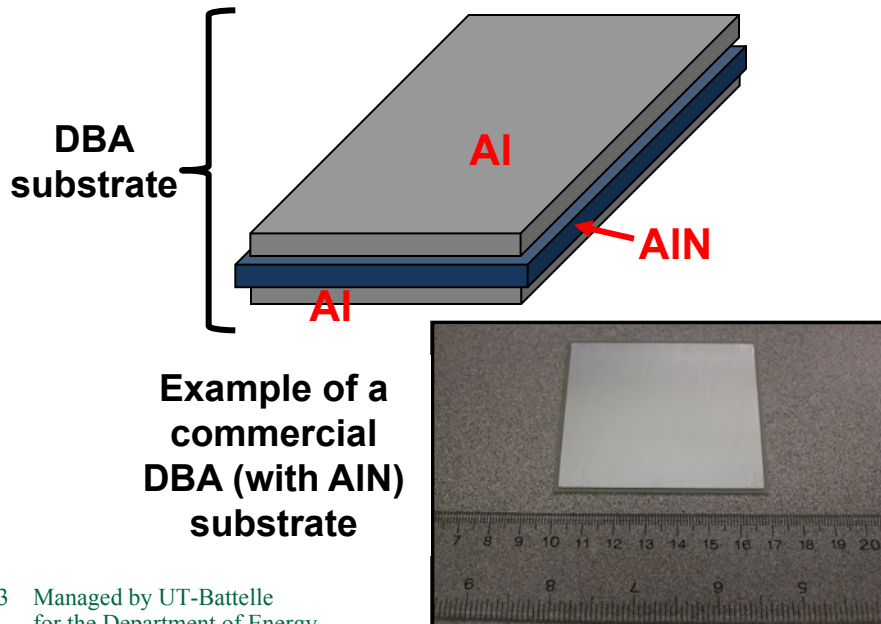
Partners

- **NTRC – ORNL**
- **Marlow (thermoelectric manuf.)**
- **Materion (metal cladding supplier)**

* VTP Multi-Year Program Plan 2011-2015

Objectives

- Develop low-cost, high quality, and thermomechanically robust direct-bonded aluminum (DBA) substrates.
- Use ORNL's in-house unique processing capabilities to fabricate innovative DBA substrates using a process that is amenable for mass production and that produces high adhesive strength of the ceramic-metal interfaces.
- Consider the fabrication and use of low-cost AlN as a potential (and alternative) contributor.



Example of Al to AlN bonding in 2010 Prius IGBT

Photo used with permission of Z. Liang (NTRC/ORNL)

Milestones

- **FY13 - 1: Complete optimization of fabrication processing parameters for DBA substrates with alumina (Al_2O_3) and aluminum nitride (AlN) ceramic.**
- **FY13 - 2: Complete fabrication of silicon nitride (Si_3N_4) ceramic substrates with both high mechanical properties and thermal conductivity.**
- **FY13 – 3: Complete development of DBA and/or direct bonded copper (DBC) substrates with high performance silicon nitride ceramics (may not be completed due to budget changes).**

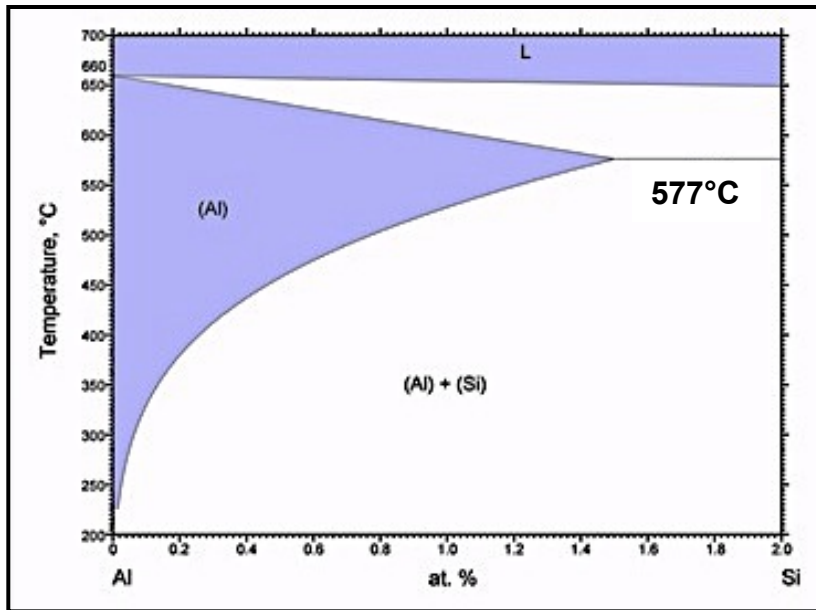
Technical Approach

- **Study patent and open literature for DBA fabrication.**
- **Identify alternative processing method to fabricate large-sized DBA substrates that has potential for low-cost manufacture. This is the first primary step in creating availability of low-cost DBA substrates.**
- **Benchmark existing commercial DBA substrates for eventual comparison against DBA substrates fabricated in this project. Also, benchmark select commercially available DBC substrates.**
- **Develop Si_3N_4 material with both high mechanical and thermal properties for ceramic substrate fabrication.**
- **Develop test method to measure interfacial shear strengths of the Al-ceramic interface.**

Accomplishments

Many Bonding Methods Were Considered

Al-Si phase diagram



Al-Si exhibits an eutectic phase at ~577°C

- Transient Liquid Phase (TLP) process via CVD Si film
- Brazing process via Al-Si alloy film

➤ Approaches taken in this subtask:

- Commercial Al-11Si brazing paste (DayBraz 729, Johnson Manufacturing Co.)
- Al-Si alloy foil (All Foils, Inc.)
- Al-Si tape prepared from powders via atomization process (READE Advanced Materials)
- Si tape prepared from powders (Vesta Si)

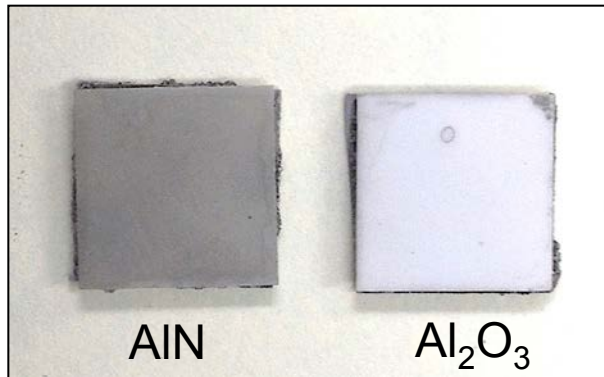
➤ Hot press conditions:

- 580 – 600°C
- 5 MPa
- Argon or N₂

Accomplishments (continued)

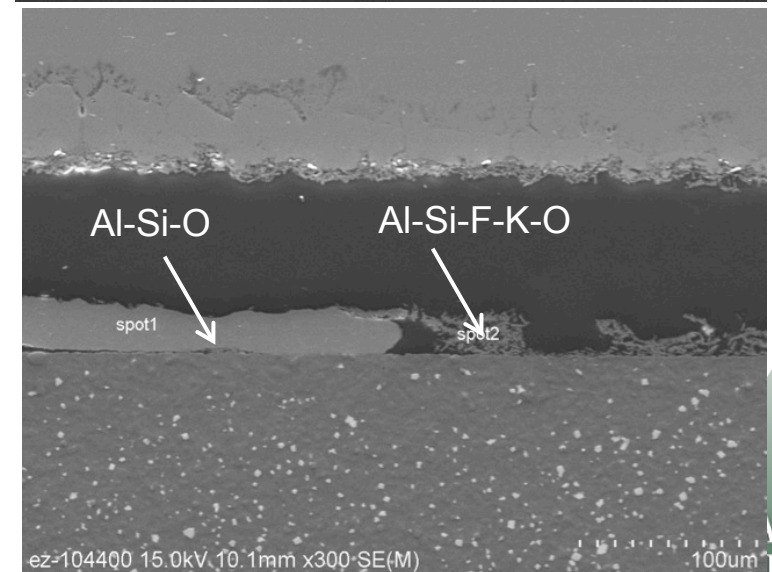
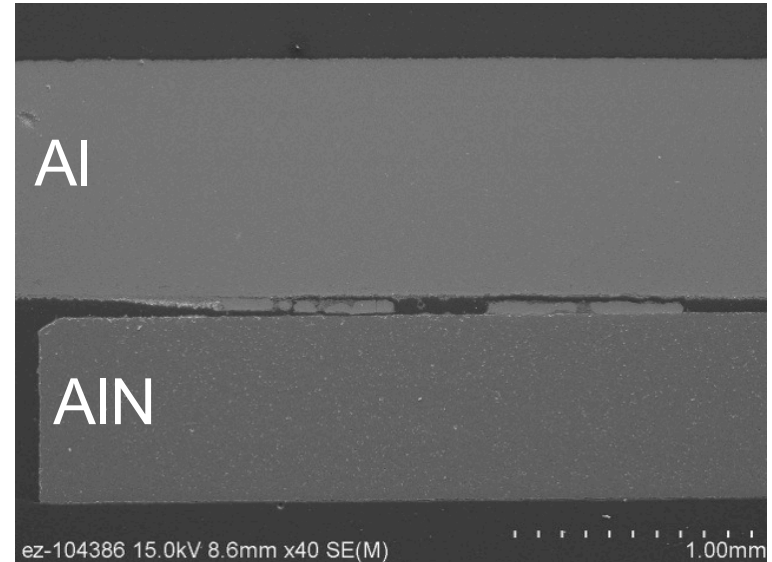
Insufficient Bonding Resulted in Early Trials

ORNL DBA substrates via
Al-11Si brazing paste



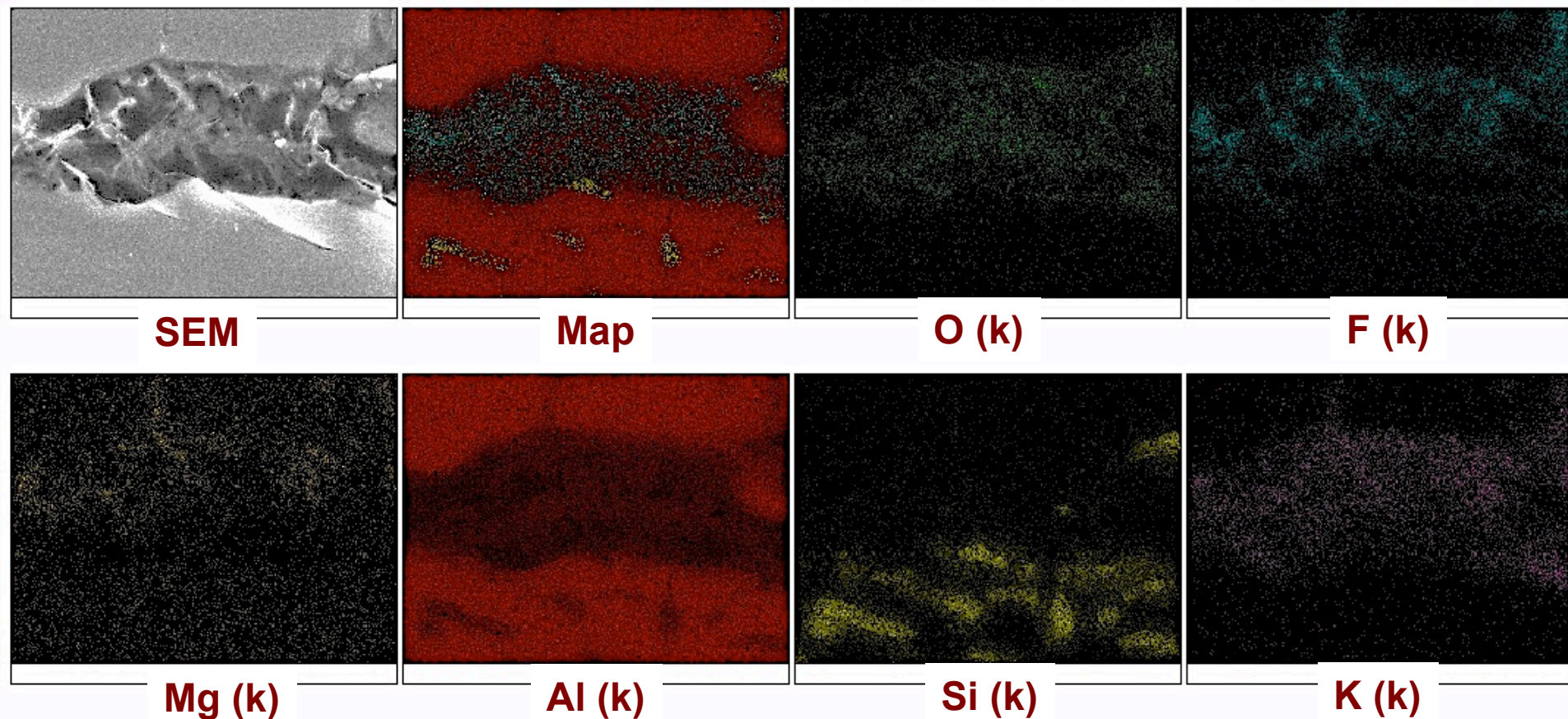
Visual inspection looked sound, but they could be readily peeled off by hand, indicative of poor bonding.

- Low vacuum in the hot-press could cause oxidation of Al plate and paste prior to joining.
- Completed instrumentation of a mechanical testing system with high vacuum furnace.



Accomplishments (continued)

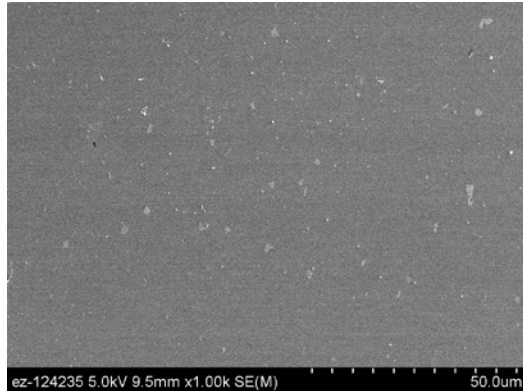
Uncompleted Reaction of Al-Si Paste Combined with High Oxygen Content Were Probably the Cause of Poor Bonding



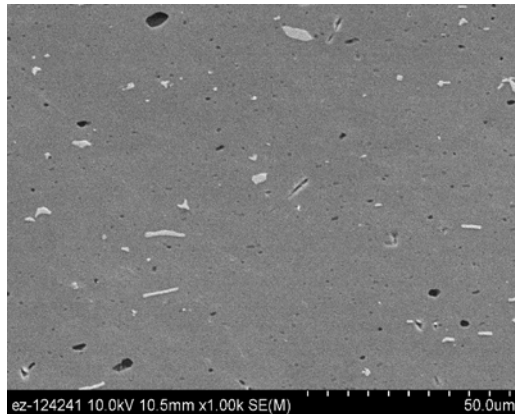
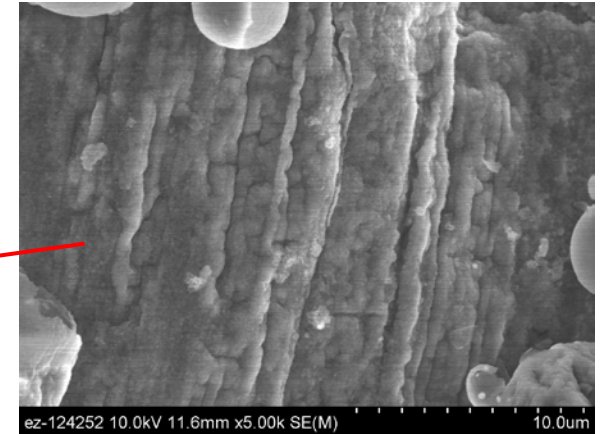
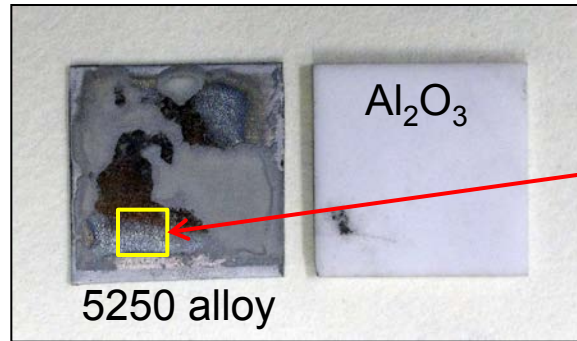
SEM EDAX element map of ORNL DBA substrate bonded with commercial Al-11Si brazing paste

Accomplishments (continued)

Poor Wettability Existed Between Both Grades of Al-Si Foil and Ceramic Substrate

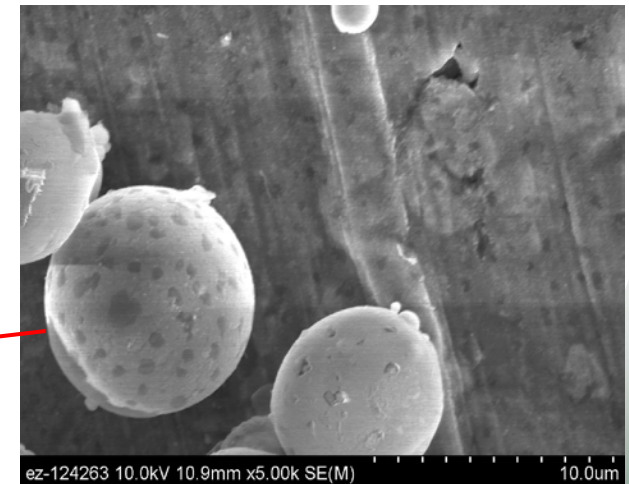
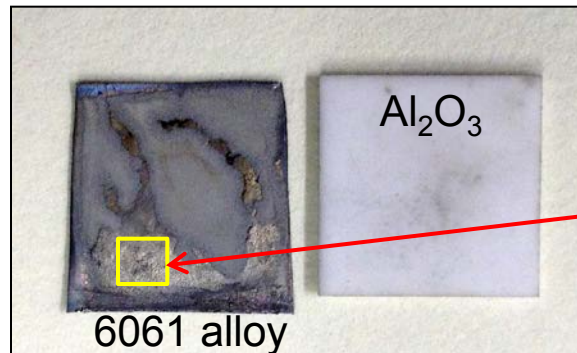


5250 alloy (Al-Mg-Mn-Si)



6061 alloy (Al-Si-Cu-Cr)

Hot press at 610°C in N₂



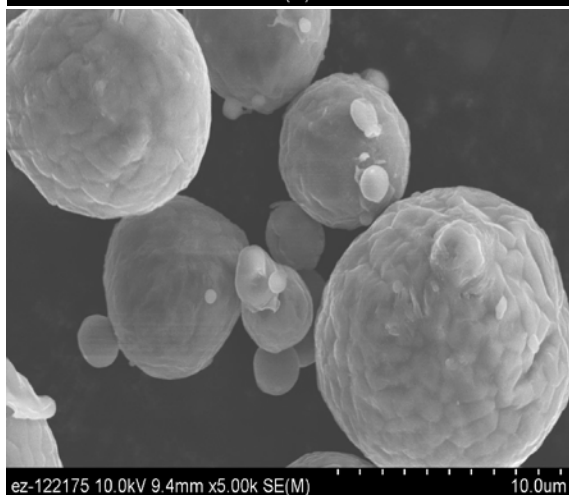
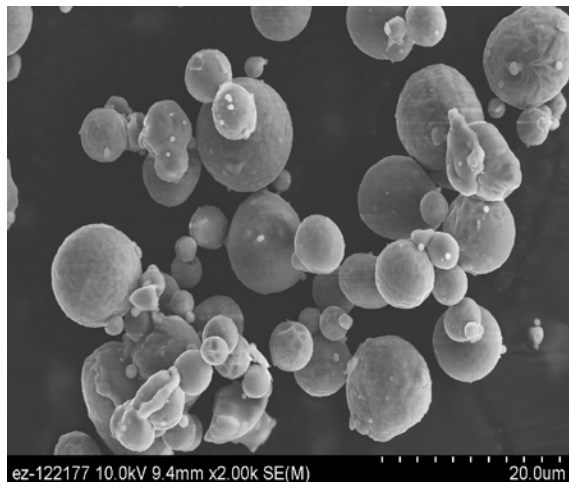
SEM micrographs of polished cross section of as-received Al-Si alloy foils

SEM micrographs of Al plate surface after bonding

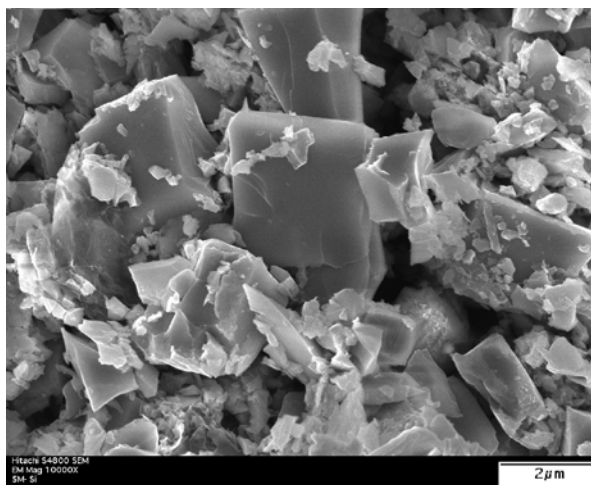
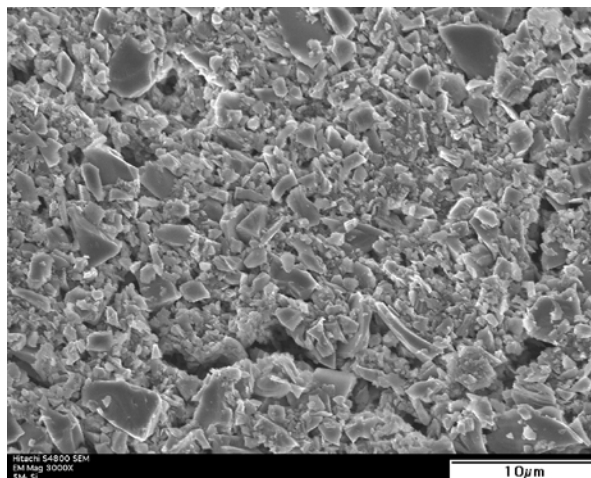
Accomplishments (continued)

Microstructure of Al-Si-Mg and Si Powders

READE Advanced Materials



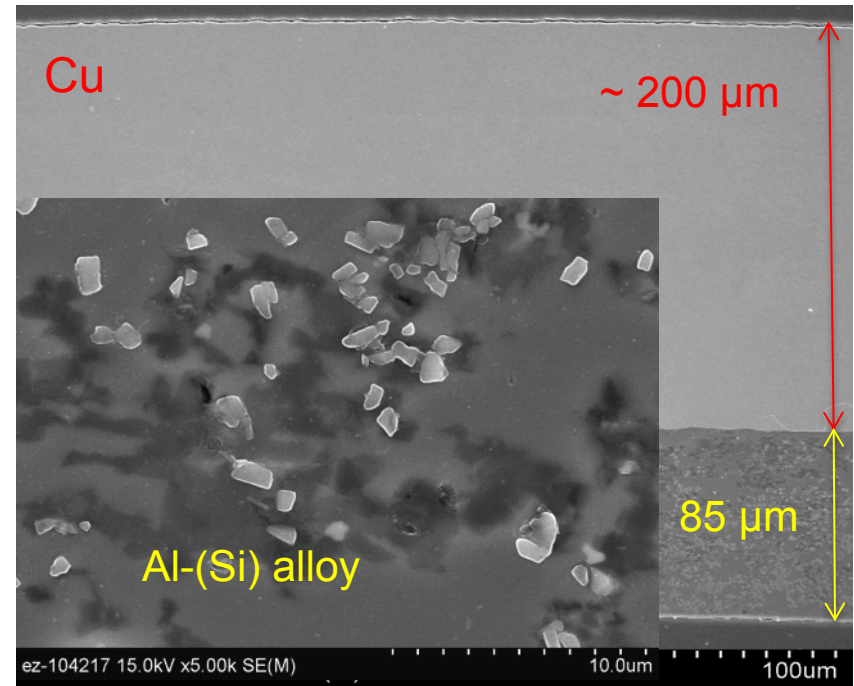
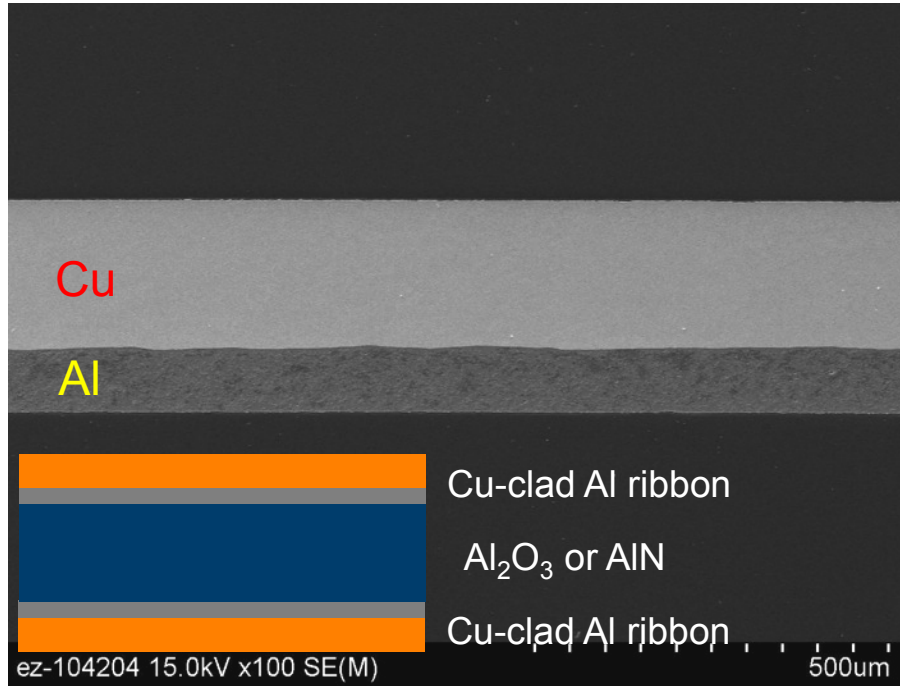
SicoMill® Si powder (Vesta Si)



Al-Si and Si film prepared by tape casting will be used to bond Al and Al₂O₃ (AlN) ceramic in the remaining FY13.

Accomplishments (continued)

Cu-clad Al foil was Evaluated as a Candidate Cladding

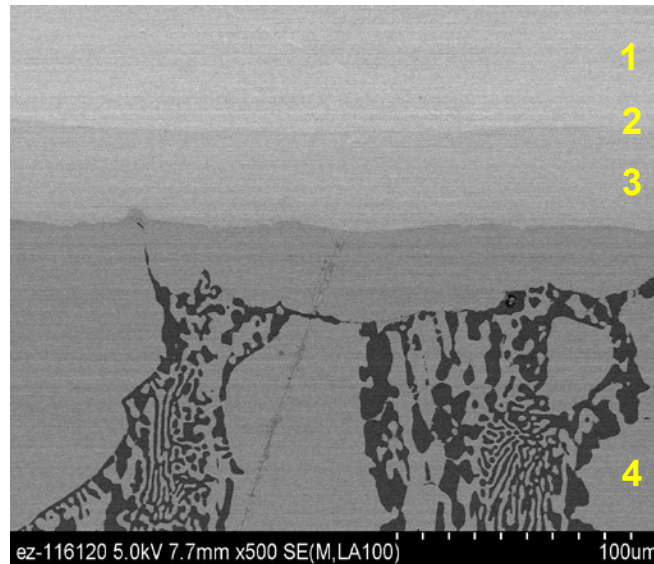
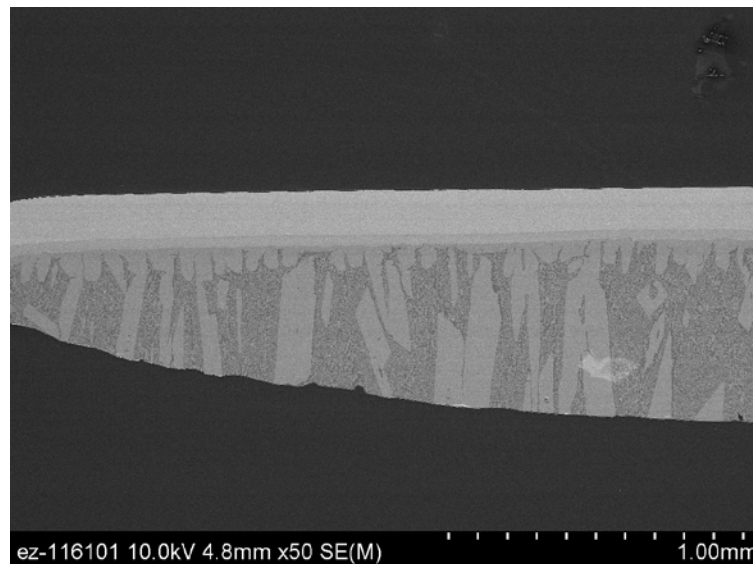


Developmental Cu-clad Al foil was acquired from Materion Corp., Cleveland, OH.

- The Cu-clad Al material could eliminate the need for interfacial brazing layer.
- Cu-clad Al material exhibits 45% higher thermal conductivity and 30% higher current density.

Accomplishments (continued)

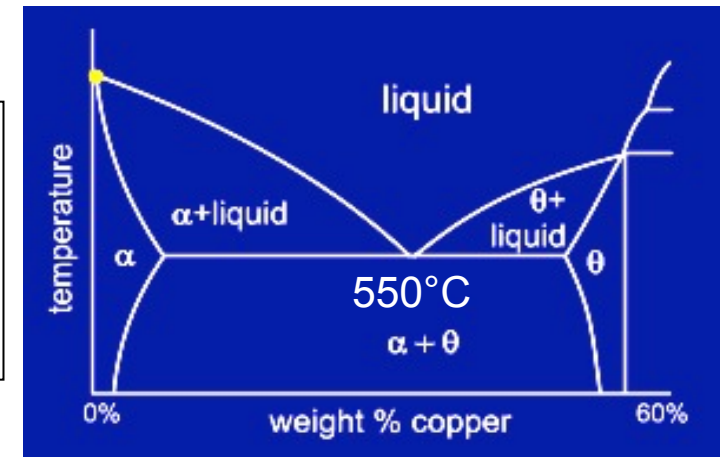
Poor Bonding Resulted Between Cu-Clad Al Foil & Ceramic



- 1: 100% Cu
- 2: 79%Cu-21%Al
- 3: 75%Cu-25%Al
- 4: 53%Cu-47%Al

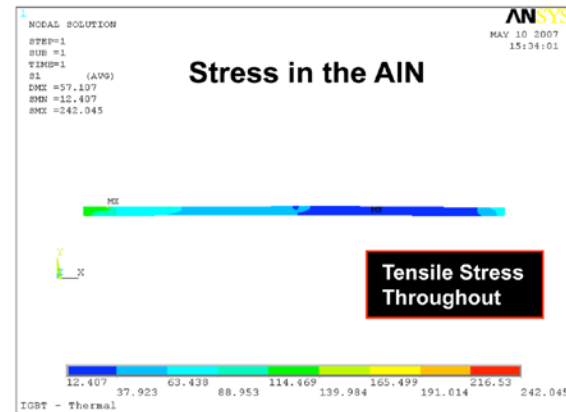
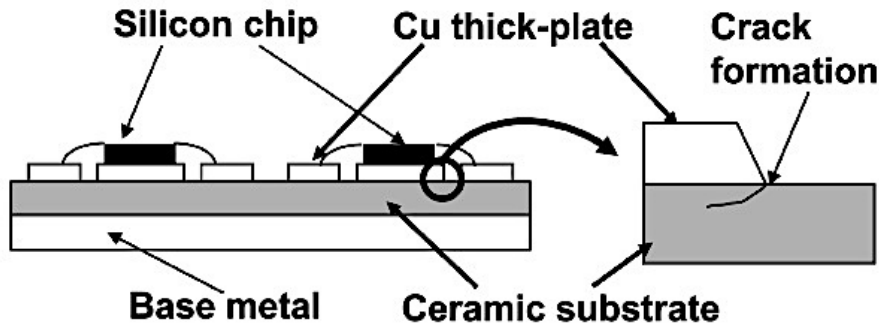
Polished cross section of Cu-clad Al foil after joining

- Cu-Al exhibits an eutectic point at 550°C lower than Al-Si eutectic point of 577°C
- Active brazing alloy might be needed to prevent early Al-Cu eutectic formation

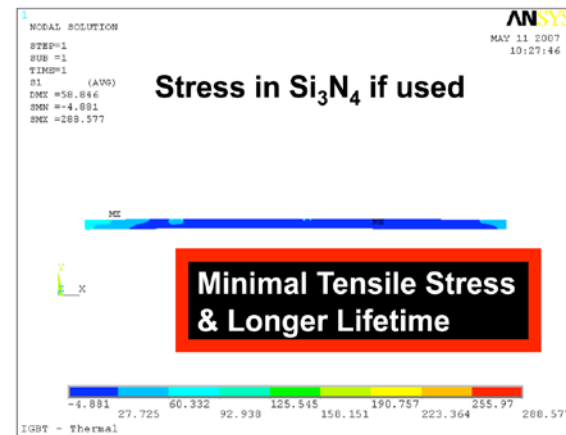


Accomplishments (continued)

Wide Band Gap Technology (GaN or SiC) Requires High Performance Substrates Such as Si_3N_4 DBC Substrates



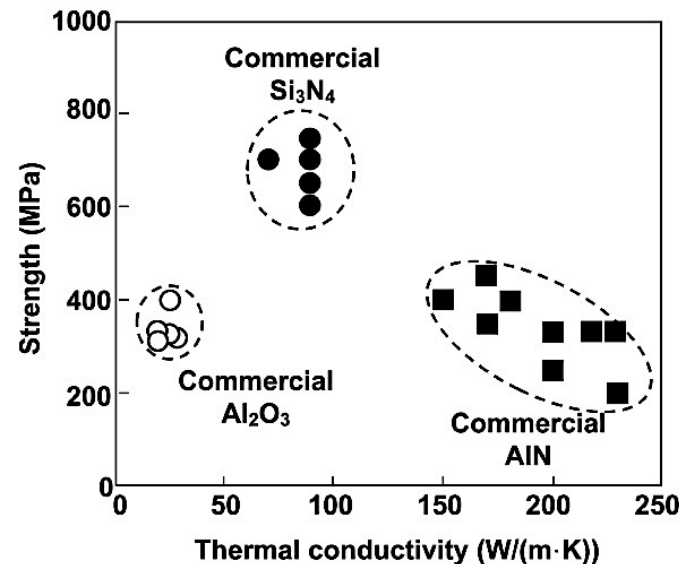
$\sigma = 400$ MPa
 $m = 13$
 $K_{IC} = 3$ MPa $\cdot\text{m}^{0.5}$



$\sigma = 800$ MPa
 $m = 18$
 $K_{IC} = 6$ MPa $\cdot\text{m}^{0.5}$

FEA
 Wereszczak

Courtesy of
 Hirao Kiyoshi,
 AIST, Japan

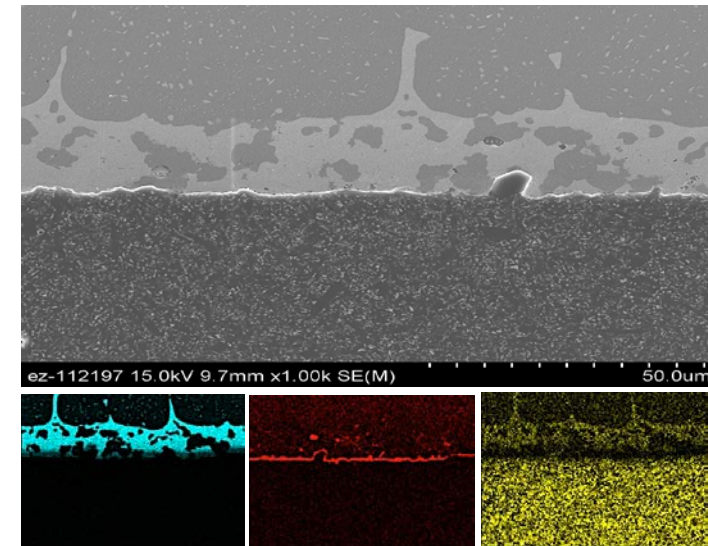
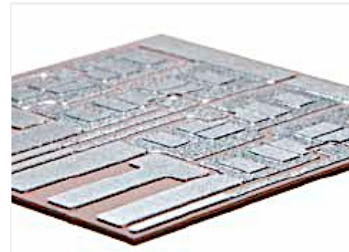
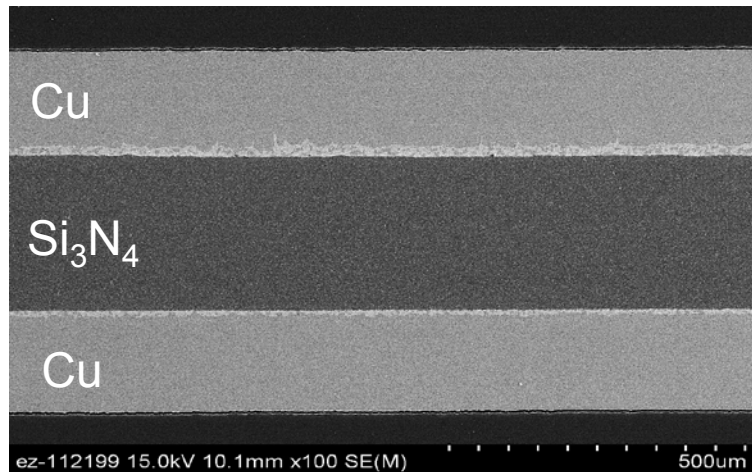


The use of Si_3N_4 ceramic substrate (1/2 of AlN thickness) with excellent mechanical performance could minimize tensile stress and thus improve mechanical reliability

Accomplishments (continued)

Si_3N_4 DBC Substrates Have Better Mechanical Reliability Than Traditional Substrates

Kyocera AMT DBC



Ag

Ti

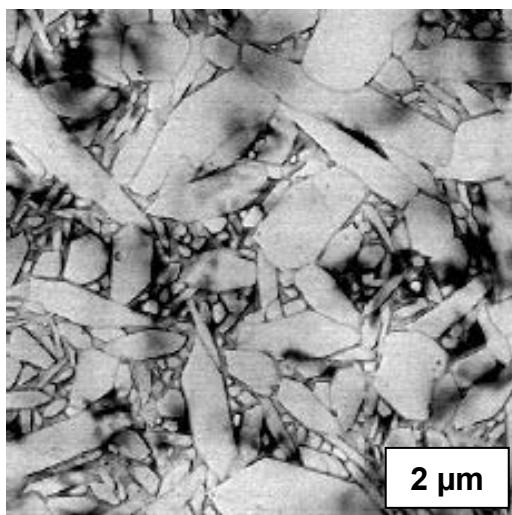
Mg

Supplier	Flexure Strength (MPa)	Fracture Toughness (MPa $\cdot\sqrt{\text{m}}$)	Thermal Conductivity (W/m $\cdot\text{k}$)
Commercial AlN	400	5	150 - 200
Kyocera SN460	850	5	60
Toshiba SN90	650	6.5	90
Curamic SN*	650	6.5 - 7	90

*Curamic (Rogers Corp.) officially demonstrated new Si_3N_4 DBC substrates at eCarTech, Munich, Oct 2012

Accomplishments (continued)

ORNL Si_3N_4 Ceramics Exhibit Comparable or Superior Mechanical Properties to Commercial Ones



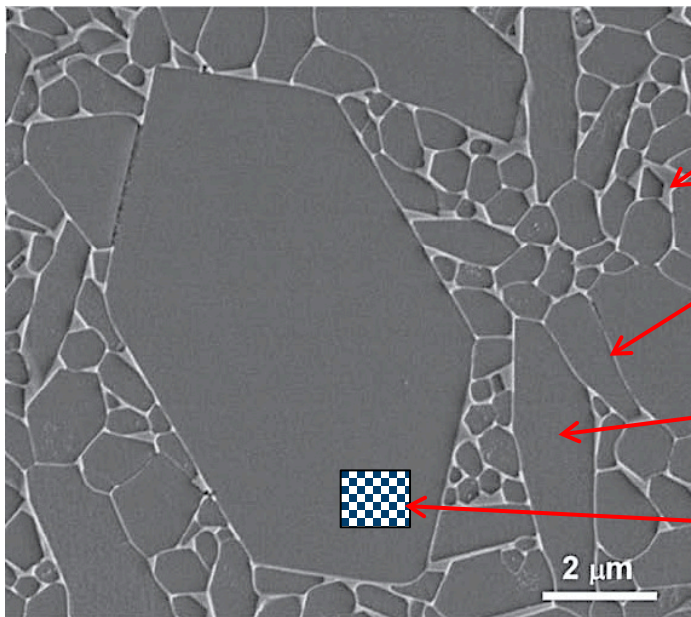
Composition	Flexure Strength MPa @ 22°C	Flexure Strength MPa @ 1200°C	Fracture Toughness MPa $\cdot\sqrt{\text{m}}$
SN8La2Mg	1140	832	10-13
SN8Gd2Mg	1226	906	11
SN8Lu2Mg	1040	894	11-13
SN8La2Si	947	-	10
SN8Gd2Si	997	803	8
SN8Lu2Si	942	-	10
NT154	950	-	6
SN147	700-800	-	6
SN240	1000	-	10

*US patent: US 7,968,484 B2
Becher and Lin*

- **SN** – developed by ORNL
- **NT154** – Saint-Gobain
- **SN147** – Ceradyne
- **SN240** - Kyocera

Accomplishments (continued)

Thermal Conductivity of Si_3N_4 Can be Tailored by Grain Boundary Microstructure and Chemistry

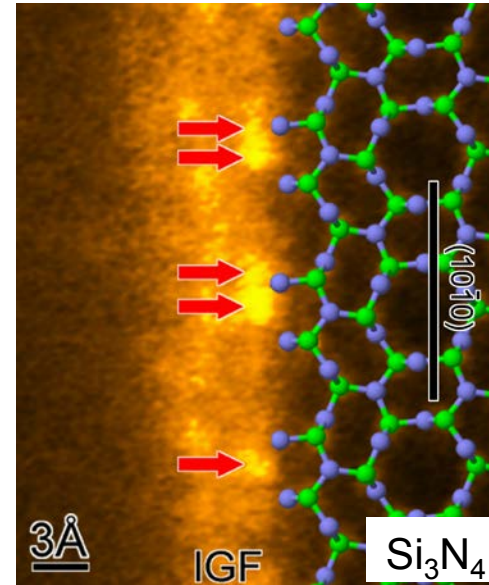


Secondary phase

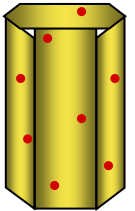
Grain boundary thin film (nm)

$\beta\text{-Si}_3\text{N}_4$ grain

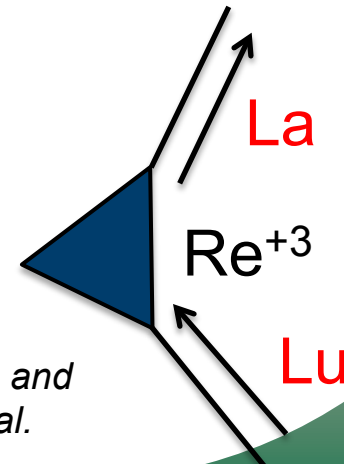
Lattice defects (lattice oxygen)



Lu



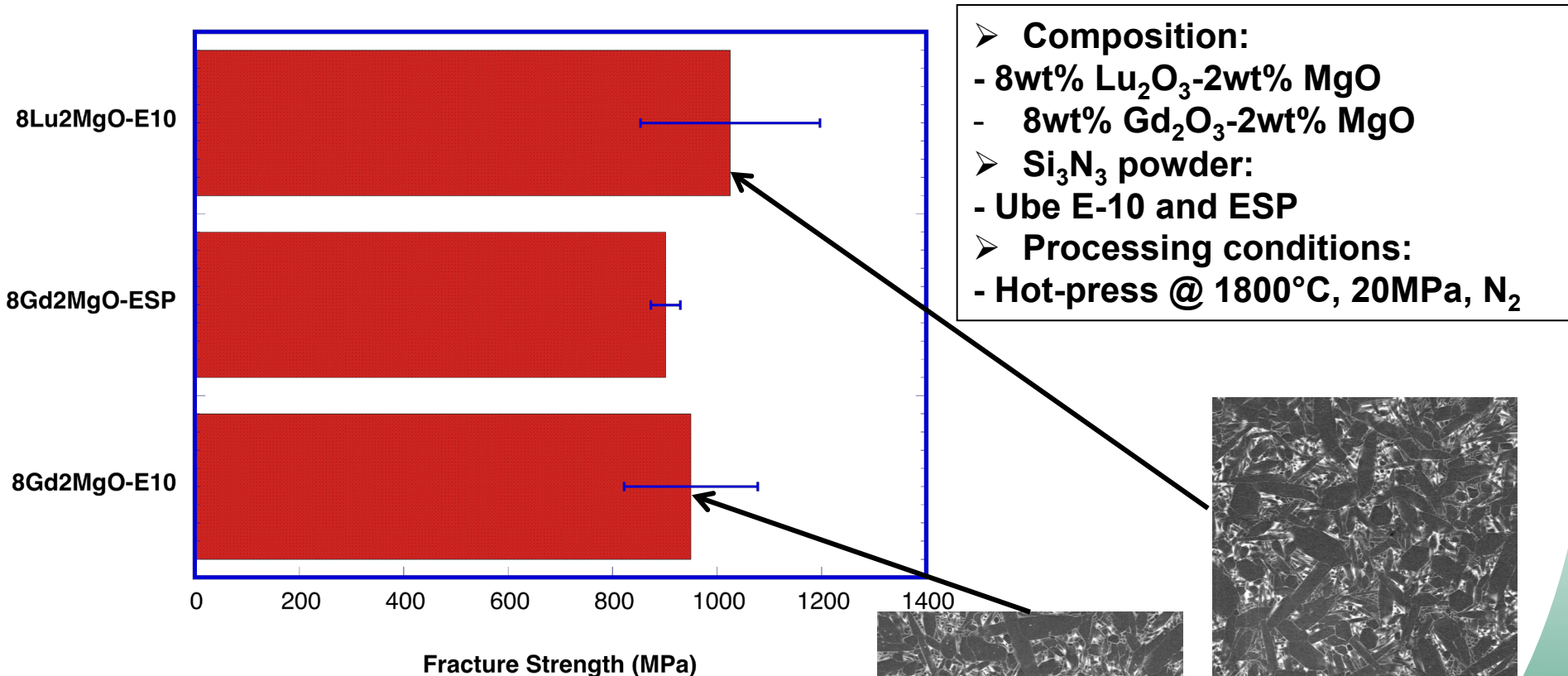
2nd phases, GB film (low thermal property) and lattice oxygen (more phonon scattering) could lower the thermal conductivity of Si_3N_4 ceramics



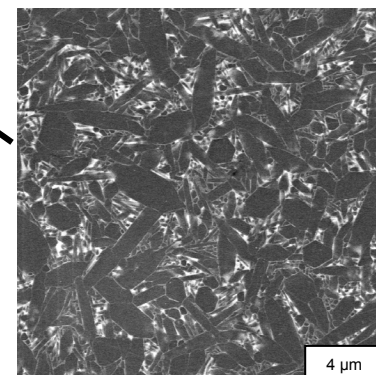
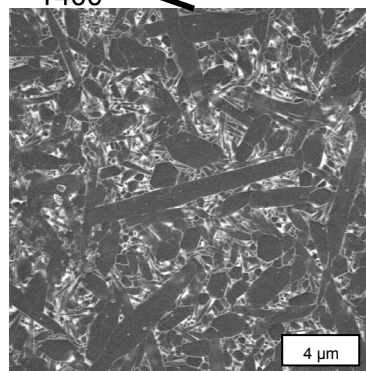
by Shibata and
Becher et al.

Accomplishments (continued)

Mechanical Strength of ORNL Si_3N_4 Ceramics Confirmed

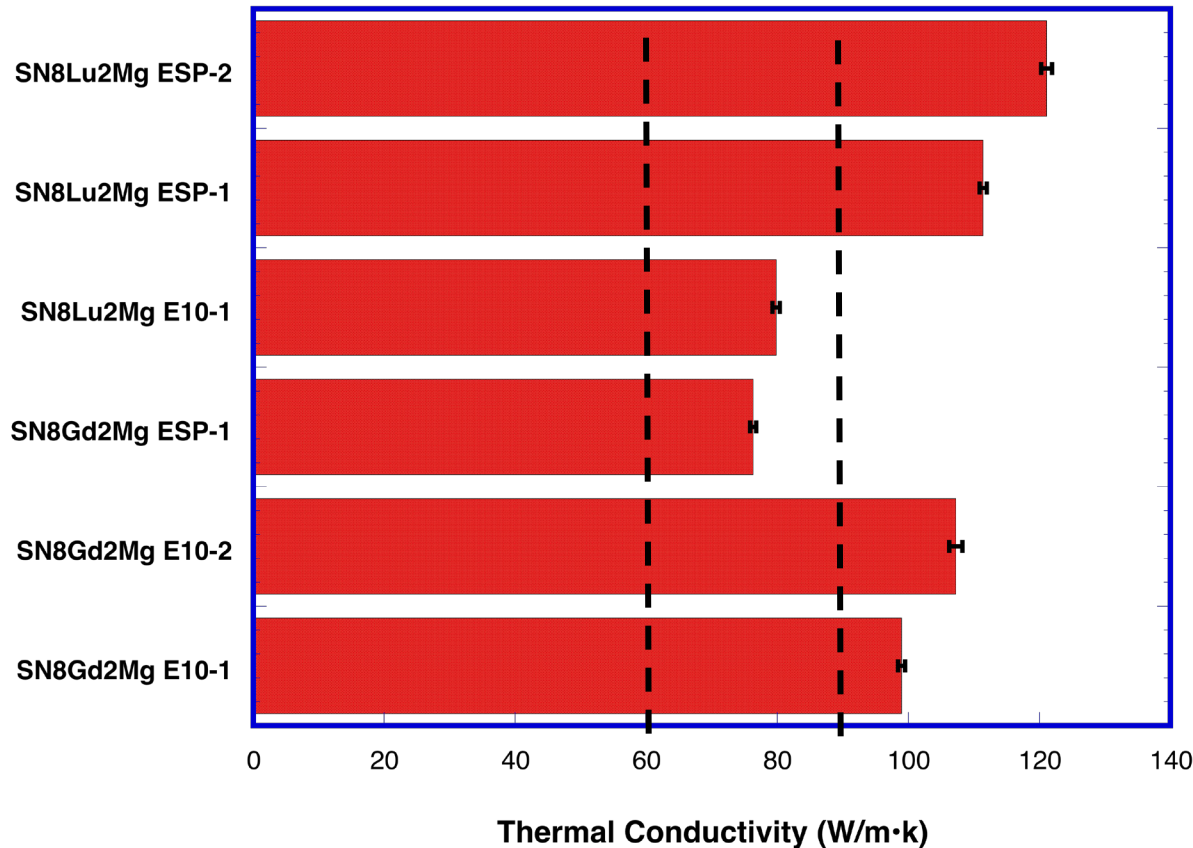


950-1100 MPa: flexure strength of ORNL specimens fabricated in 2010; JACS, 93 [2] 570–580 (2010)



Accomplishments (continued)

ORNL Si_3N_4 Ceramics Exhibit Comparable or Superior Thermal Conductivity to Commercial Si_3N_4



- Kyocera SN460:
60 W/mk

- Toshiba SN90:
90 W/mk

- Curamic SN:
90 W/mk

Manufacturers reported data

Measured by laser flash method

Thermal property could be further enhanced by engineering control of Si_3N_4 grain size, oxygen content, and crystallinity of 2nd phase

Collaborations

➤ Partners

- ✓ **Advanced Power Electronics and Electric Motors R&D team members at NTRC of ORNL.**
- ✓ **Electric and Electronic Tech Team provided constructive input.**
- ✓ **Marlow (established thermoelectric manufacturer) provided their DBA substrate for ORNL to assess and conduct bench mark test.**
- ✓ **Materion provided the Cu-clad Al ribbon with tailored thermal and electric property.**

➤ Technology transfer

- ✓ **Potential with Marlow, GM or Delphi on the development of high performance DBA/DBC substrates with Si_3N_4 ceramic substrate.**
- ✓ **Development of high performance DBA substrate with Si_3N_4 ceramic substrate would provide the high-power and high-temperature challenge for IGBT and MOSFET with SiC or GaN wide band gap material.**

Future Work

- **Complete fabrication of tape-cast Al-Si thin film using atomization Al-Si powders for bonding Al-AlN (and Al_2O_3) substrates. (FY 13)**
- **Complete fabrication of tape-cast Si thin film using commercial Si powders for bonding Al-AlN (and Al_2O_3) substrates. (FY13)**
- **Complete optimization of Si_3N_4 ceramic with both high mechanical and thermal properties for power electronic ceramic substrates. (FY14)**
- **Develop low-cost Si_3N_4 ceramic using high purity Si powders via sinter-reaction bonded process. (FY14)**
- **Fabricate DBC (and DBA) substrates using reaction-bonded Si_3N_4 ceramics via Ti-containing active brazing element, and tech transfer and commercialize the products. (FY15)**

Summary

- **Relevance:** low cost and robust DBA substrates to improve reliability of power electronic device.
- **Approach:** develop low cost and reliable DBA substrates with AlN and Si₃N₄ ceramic via brazing and/or metallurgical process.
- **Collaboration:** EETT, substrate manufacturers, and materials suppliers.
- **Technical Accomplishments:**
 - ✓ Results confirm compromise between low cost and reliability must be struck.
 - ✓ Processing and characterization of DBA substrates with Al-Si paste and Al-Si foil.
 - ✓ Characterizations of Al-Si and Si powders
 - ✓ Re-produce ORNL Si₃N₄ ceramics with consistent excellent mechanical strength
 - ✓ Thermal property measurements of ORNL Si₃N₄ ceramics
- **Future Works:**
 - ✓ Optimization of Si₃N₄ ceramic with both high mechanical and thermal properties.
 - ✓ Development low-cost Si₃N₄ ceramic using high purity Si powder
 - ✓ Fabrication of DBC (and DBA) substrates using reaction-bonded Si₃N₄ ceramics and tech transfer and commercialize the products.